

Design and Optimization of Graphene-On-Silicon Nitride Integrated Waveguide Mode Filters

F. Martín-Romero, F. J. Díaz-Fernández and V. J. Gómez

Nanophotonics Technology Center, Universitat Politècnica de València, Camino de Vera s/n, 46022 Valencia, Spain.

Programa de Doctorado en Telecomunicación.

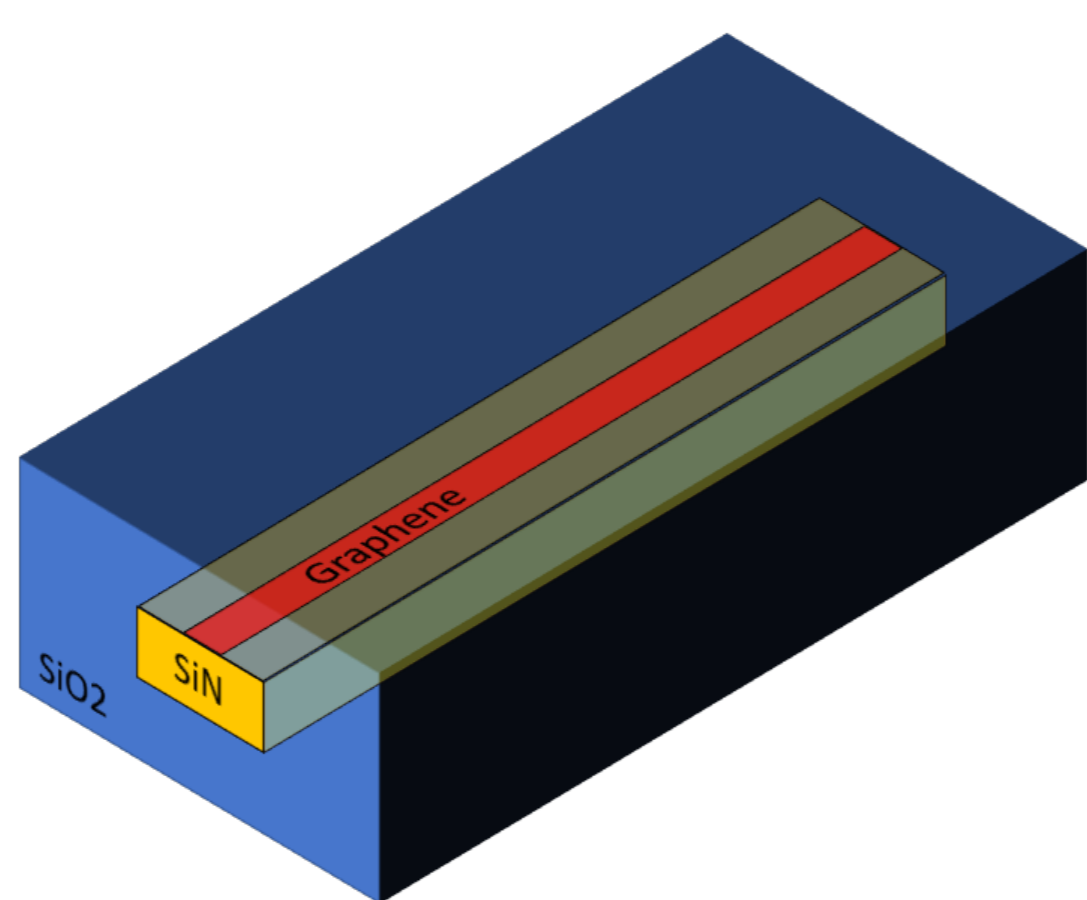
Email: fmarrom@ntc.upv.es

Abstract

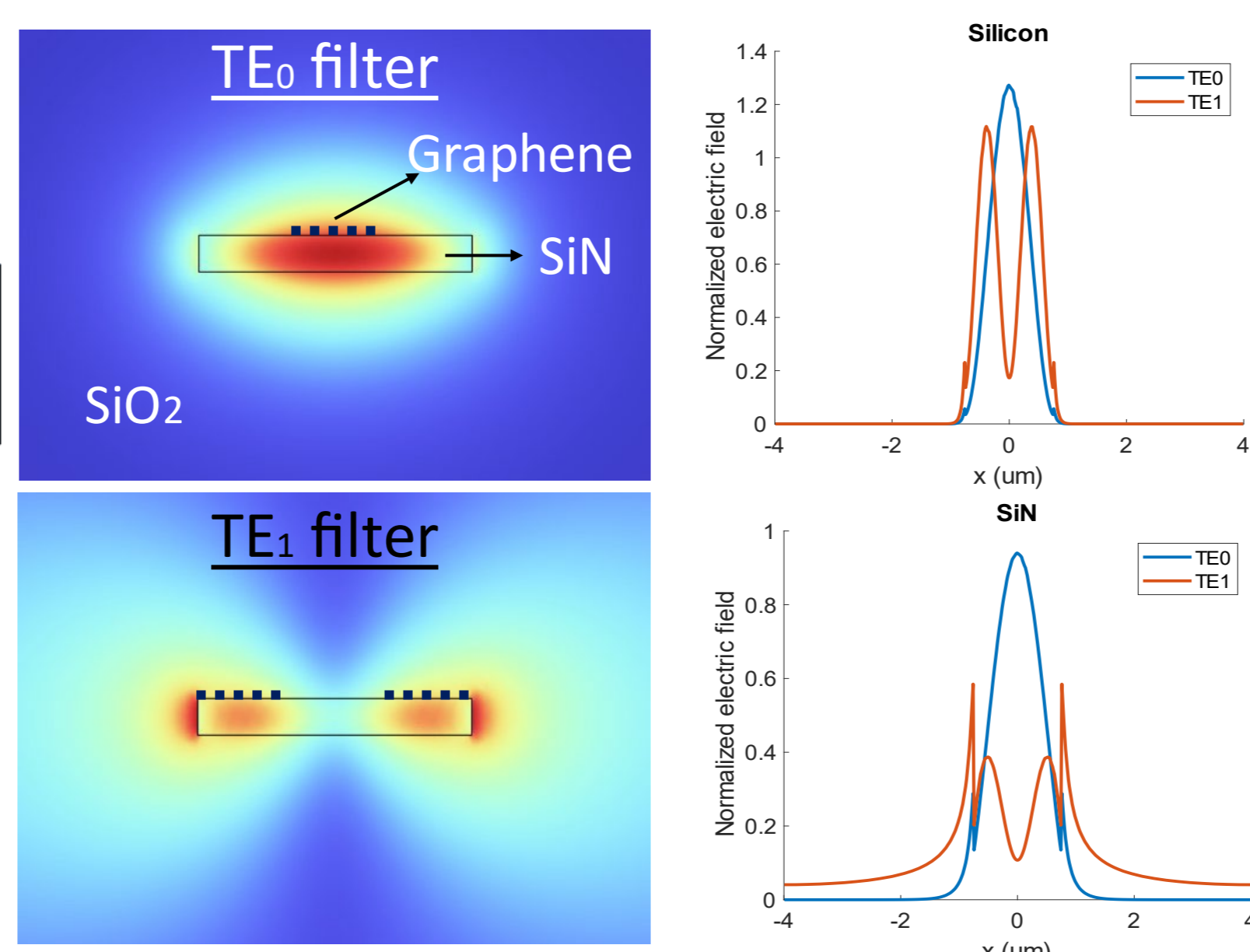
We report on the design and optimization of graphene-on-silicon nitride (GOSiN) integrated waveguide mode filters for suppressing the spurious propagation of either TE_0 or TE_1 modes. The integrated waveguide consists of a silicon nitride core partially covered by single layer graphene films. We then compare the efficiency, fabrication tolerance and bandwidth of the devices to those of similar graphene-on-silicon (GOS) integrated waveguide mode filters.

Mode Division Multiplexing (MDM):

- **Mode Division Multiplexing** increases channel capacity by transmitting **higher order waveguide modes**.
- Traditional MDM systems suffer from **high insertion losses, large device footprints and high costs**.
- Promising approach: **graphene-on-SiN integrated waveguide mode filters** [1]-[3].



Motivation and design



$$ER = \alpha_{stop} - \alpha_{pass} \quad SR = ER / \alpha_{pass}$$

$$L = C / ER \quad IL = C / SR$$

α_{stop} : Absorption coefficient of the stop mode

α_{pass} : Absorption coefficient of the pass mode

ER : Extinction Ratio

SR : Selection Ratio

C : Contrast

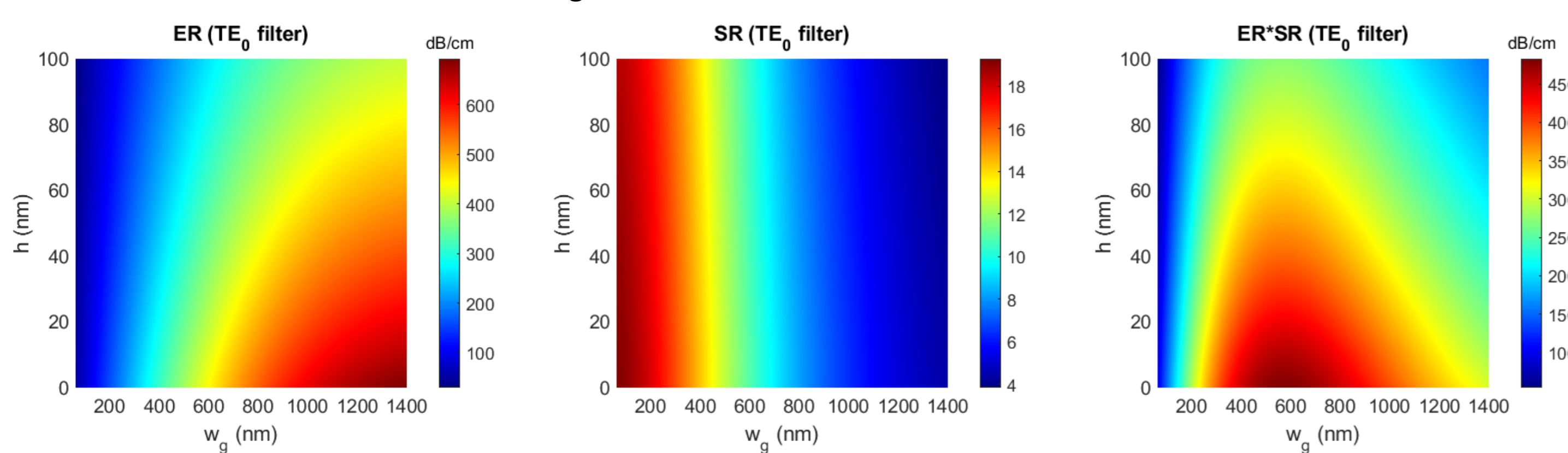
L : Device length

IL : Insertion Losses

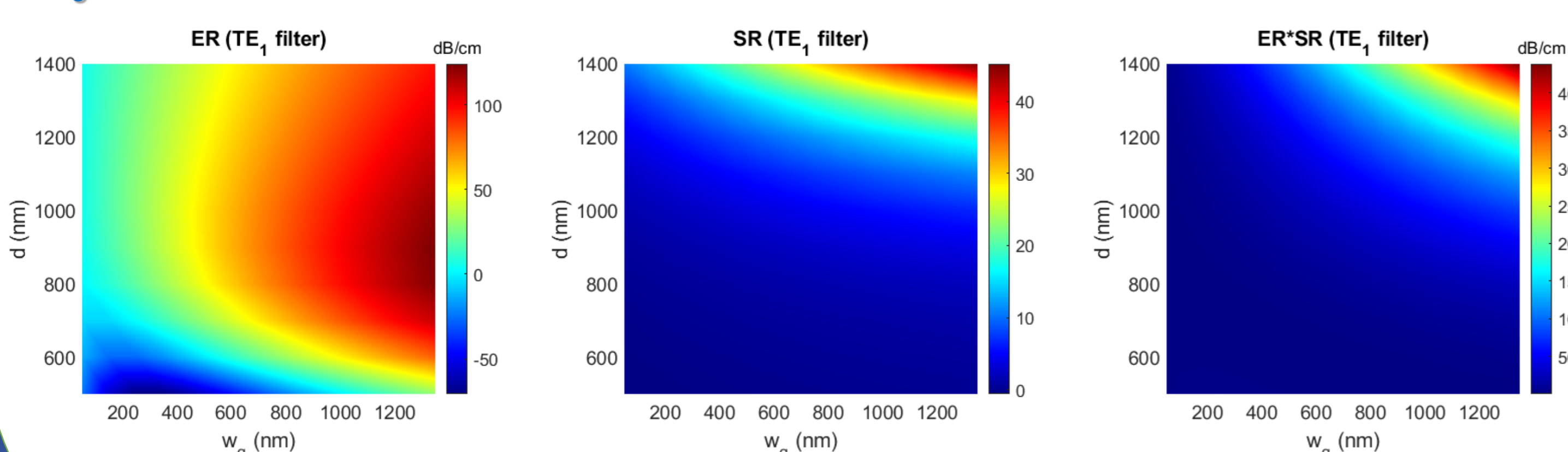
Minimize $L \times IL$
↓
Maximize $ER \times SR$

Optimization of the design

Performance of a TE_0 and a TE_1 filter with a SiN waveguide core of $W = 1500$ nm and $H = 200$ nm, at $\lambda = 1550$ nm, as a function of the graphene strips width (w_g) and separation (h – vertical, d – horizontal).



TE_0 filter: Better performance than GOS [2]. Less overlapping between modes.

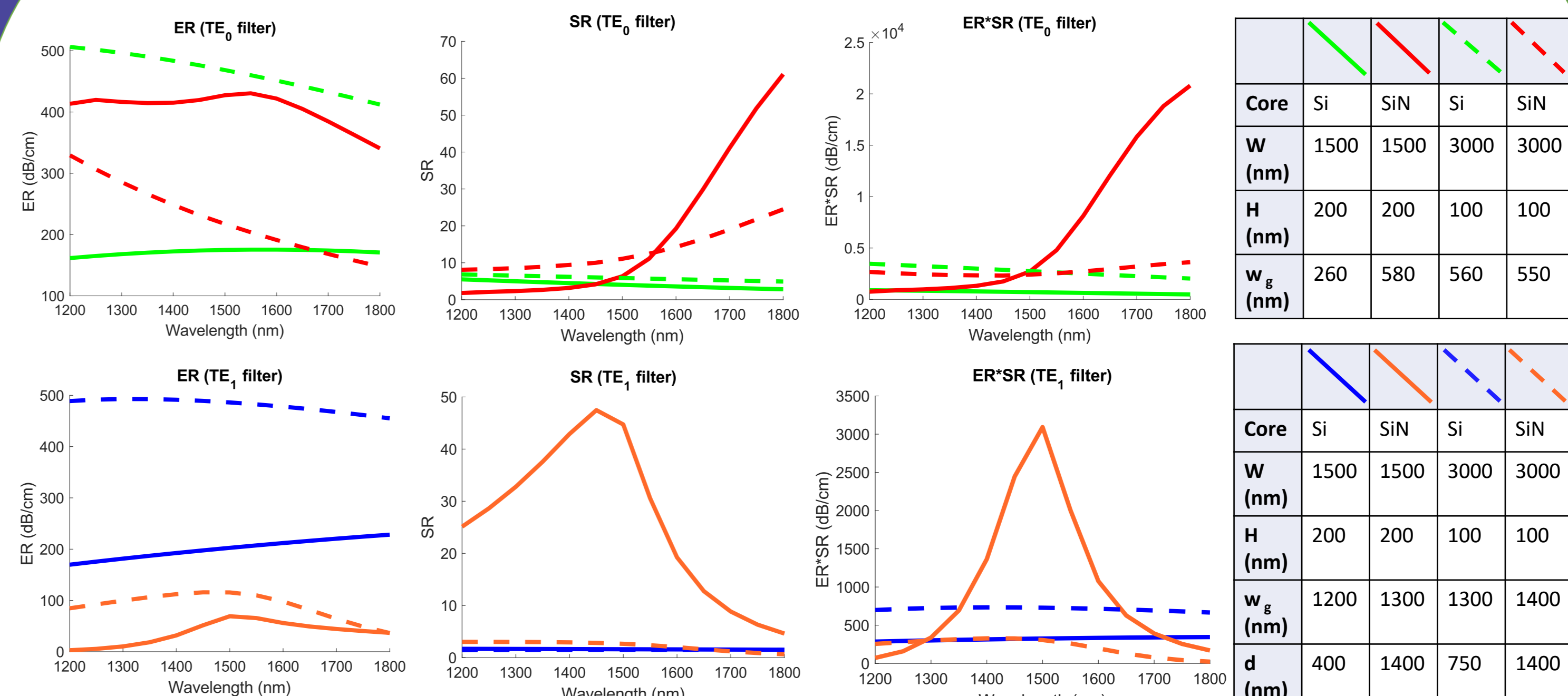


TE_1 filter: Worse ER than GOS [2], but better $ER \times SR$. Large optimal distance between graphene strips.

Fabrication tolerance of the TE_0 filter

If we define the fabrication tolerance of the TE_0 filter as the range of graphene width values in which the $ER \times SR$ product is above 90% of its maximum value, it can be observed that the tolerance for GOS filters is ± 80 nm, while for GOSiN filters it is $+180$ nm -200 nm.

Optical bandwidth



GOS
Generally larger ER (shorter device), depending on the geometry.

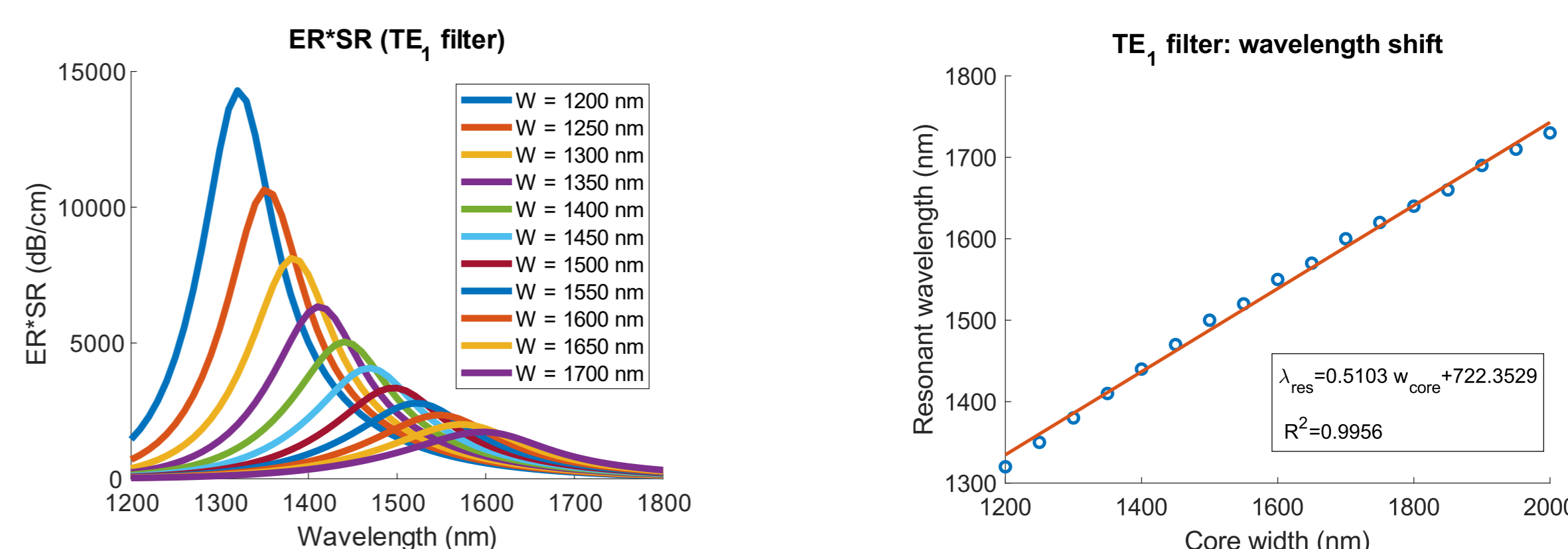
GOSiN
Much larger SR (lower insertion losses), and much larger figure of merit $ER \times SR$ (smaller product of length and insertion losses).

Homogeneous response.

Tunable resonance peak.

Wavelength tuning of GOSiN TE_1 filter

If we fix the width and position of graphene in the GOSiN TE_1 filter at $w_g=1400$ nm and $d=1400$ nm, we observe that the resonant wavelength grows linearly when the core width (W) is increased.



Acknowledgements and References

This study forms part of the Advanced Materials programme and was supported by MCIN with funding from European Union NextGenerationEU (PRTR-C17.I1) and by Generalitat Valenciana.



[1] Wang, J., Zhang, X., Chen, Y., Geng, Y., Du, Y., Li, X., 2021. Optics Communications 481, 126531.

[2] Xing, P., Ooi, K.J.A., Tan, D.T.H., 2018. Sci Rep 8, 9874.

[3] Xing, Z., Li, C., Han, Y., Hu, H., Cheng, Z., Wang, J., Liu, T., 2019. Opt. Express, OE 27, 19188–19195.

Conclusions

The proposed graphene-on-SiN integrated devices would allow to selectively filter the TE_0 or the TE_1 mode of a SiN waveguide. They show a wavelength region where the figure of merit is much larger than that of graphene-on-silicon devices, and which in the case of the TE_1 filter consists of a tunable resonant peak.